



Dr. Byoung-Ho Lee

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Byoung-Ho Lee, Ph.D., is a distinguished expert in semiconductor metrology and technology. Currently serving as a Senior Fellow at Hitachi High-Tech, he has built an impressive career over two decades. Prior to his current role, he was a Fellow at SK hynix, Director of Integrated Metrology at Nanometrics, and VP of Technologist at Ultratech. His early career began as a Principal Engineer at Samsung Electronics.

Dr. Lee earned his Ph.D. in Chemistry from KAIST in 2000 and has been actively involved in advancing semiconductor metrology. He has contributed to numerous technical committees, including SPIE Metrology, Inspection, and Process Control Program Committee (since 2006), SEMI ASMC (2012–2017, rejoining in 2025), and USA MAPT 2.0 Metrology Committee (since 2024). His leadership extends to forums such as Semicon Korea MI and the Korean International Semiconductor Conference on Manufacturing Technology.

With 40+ published papers and 11+ granted patents, Dr. Lee continues to influence semiconductor manufacturing with his expertise and innovation. His extensive research and contributions make him a key figure in the industry.